

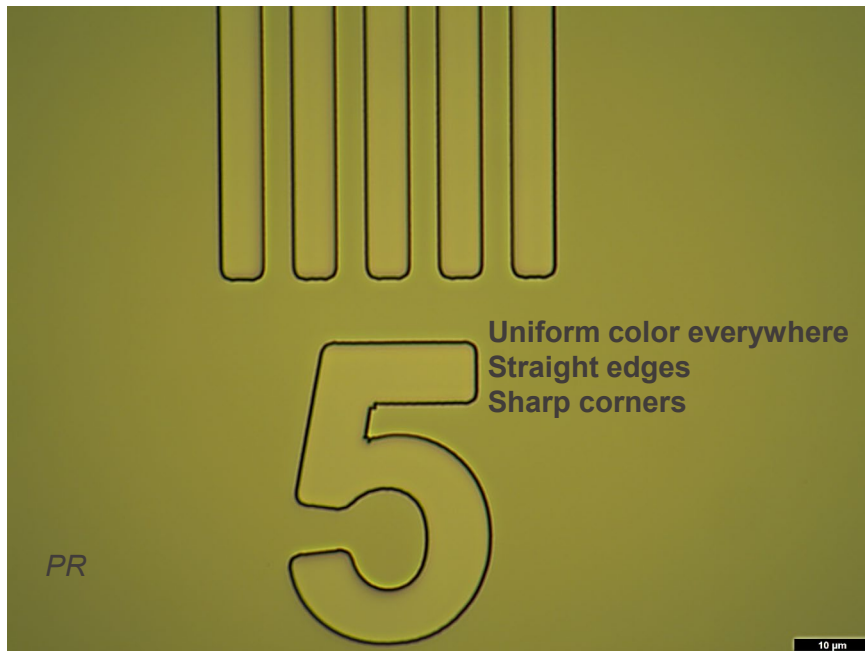
Photoresist reflow for IBE etch process

Silicon test wafer

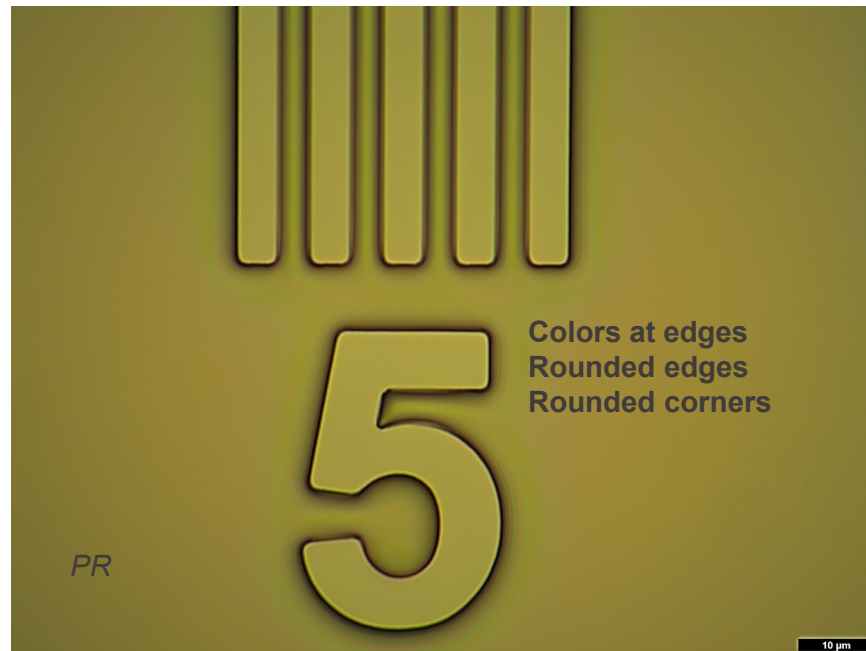
Ti/Pt sputtered (Spider)

Litho AZ 1um (ACS + MA6)

No Reflow



Reflow 2min @125°C

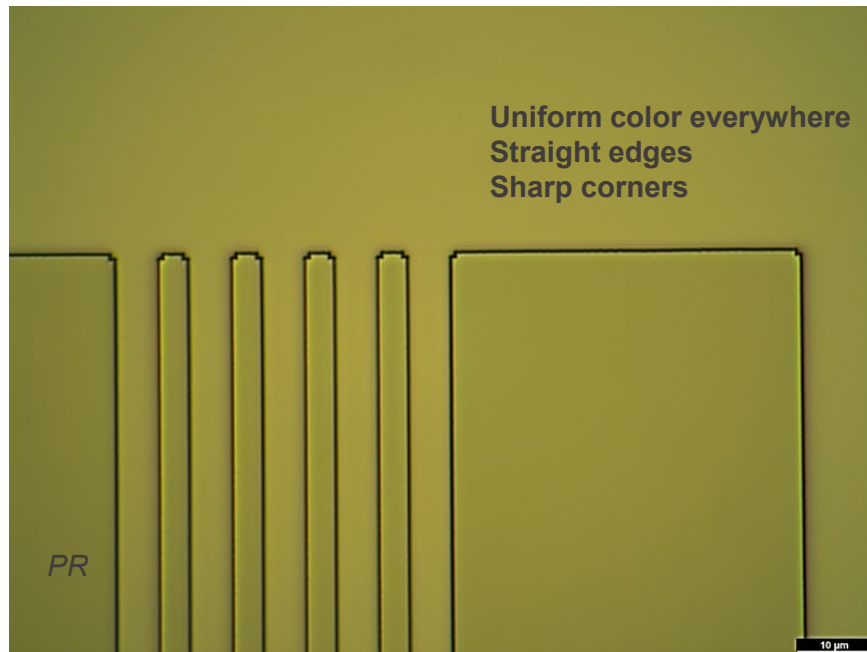


Silicon test wafer

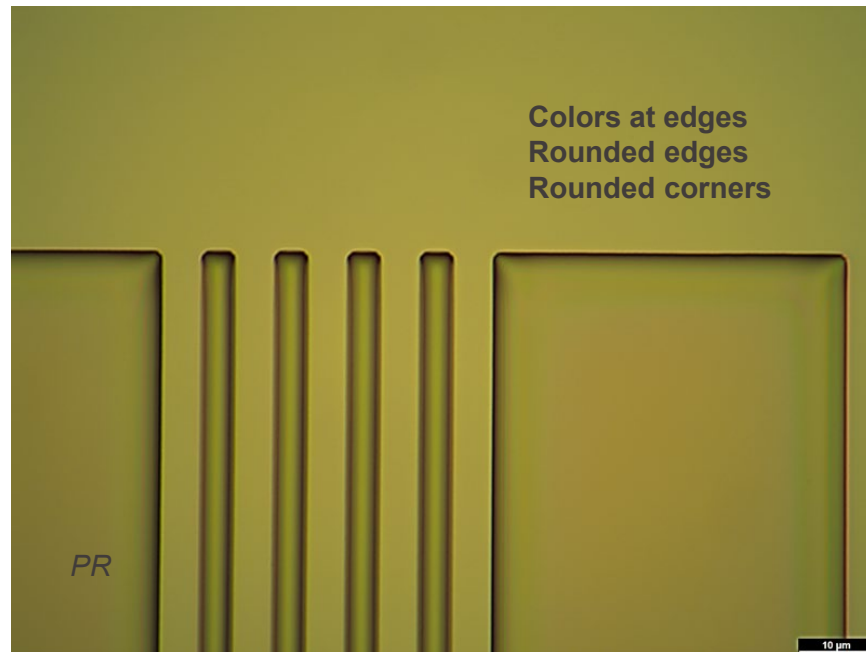
Ti/Pt sputtered (Spider)

Litho AZ 1um (ACS + MA6)

No Reflow



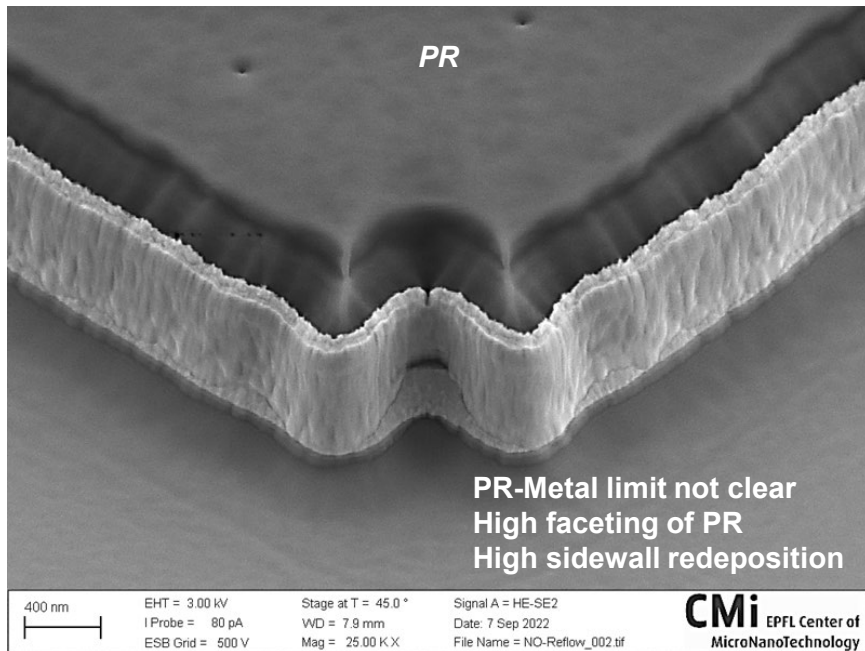
Reflow 2min @125°C



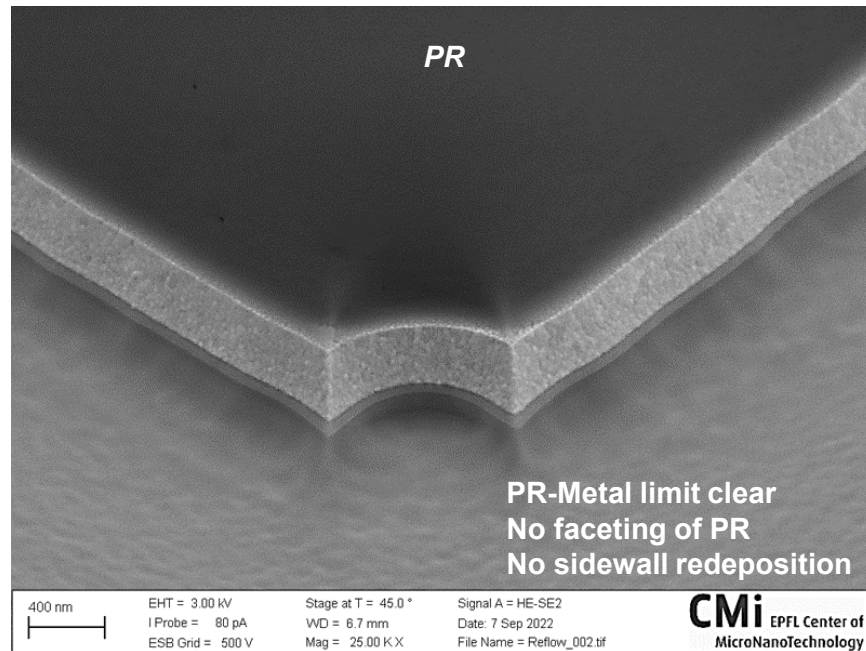
Ti/Pt sputtered (Spider)
Litho AZ 1um (ACS + MA6)

Medium_IBE, -10deg, 50% over-etch

No Reflow



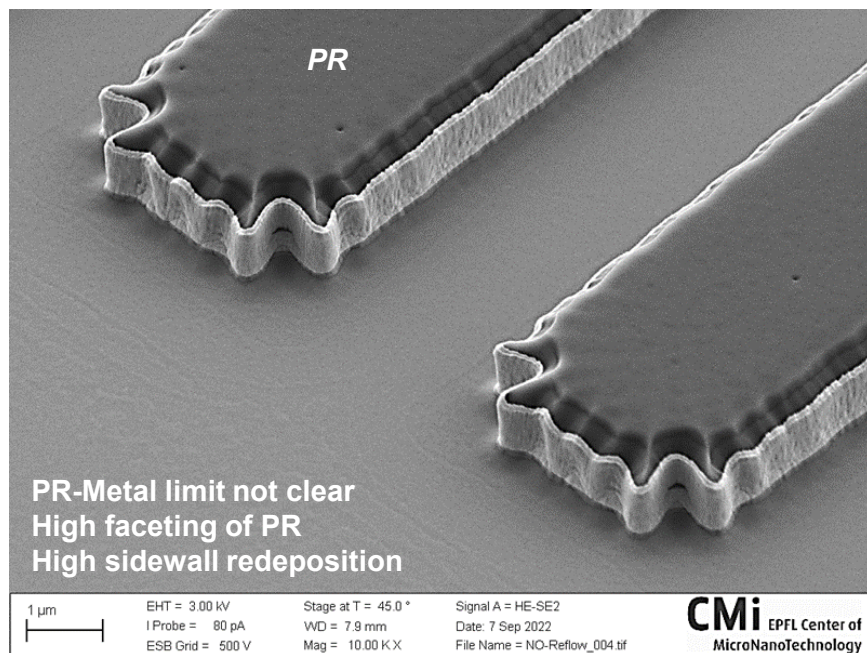
Reflow 2min @125°C



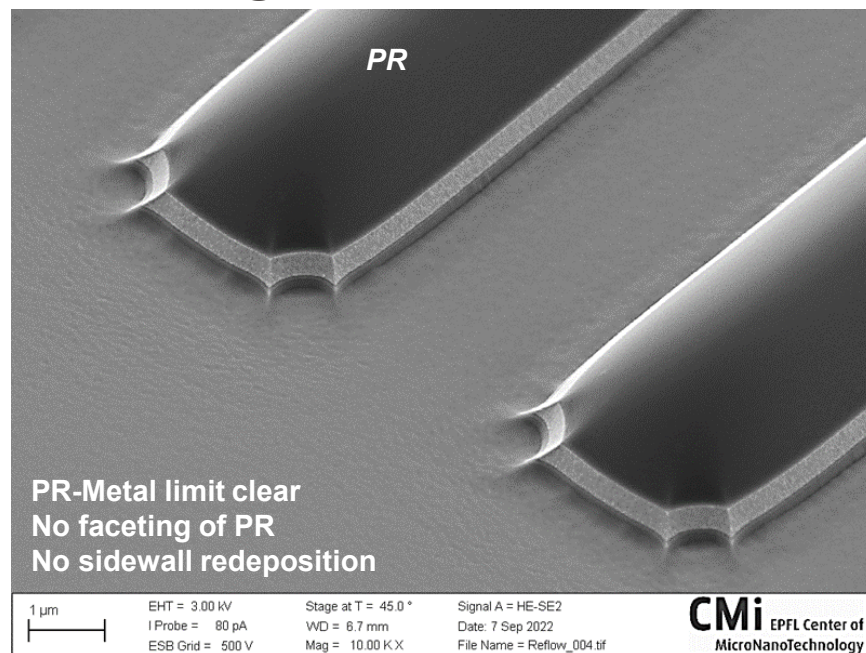
Ti/Pt sputtered (Spider)
Litho AZ 1 μ m (ACS + MA6)

Medium_IBE, -10deg, 50% over-etch

No Reflow



Reflow 2min @125°C

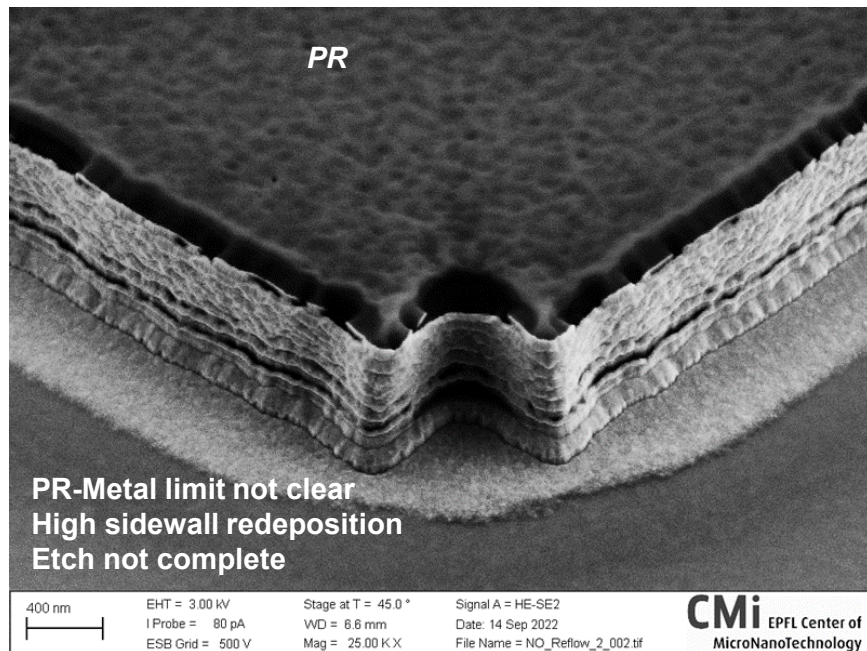


Photoresist reflow for IBE etch process

Ti/Pt sputtered (Spider)
Litho AZ 1um (ACS + MA6)

Medium_IBE, 70% @ -45deg, 30% @ -5deg, 10% over-etch

No Reflow



Reflow 2min @125°C

